

EXHIBIT A

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Semiconductor Glossary

Semiconductor OneSource

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Term (Index)	Definition
cleaning	process of removing contaminants (particles as well as metallic and organic) from the surface of the wafer; can be implemented using liquid chemicals (wet cleaning) or gases (dry cleaning).
contaminant	
dry cleaning	
metallic contaminant	
organic contaminant	
particle	

wet cleaning	
supercritical fluid	

Term (Index)	Definition
dry cleaning	
AHF, anhydrous HF	
cryogenic aerosol	high velocity frozen particles of inert gases such as CO2 and Ar; used to remove particles from the wafer surface.
hydrogen reduction, H2	during anneal in H2 ambient at temperature exceeding 900 deg. C.

UV/Cl2

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Term (Index)	Definition
Spin cleaning	spinning wafer is subjected to interactions with liquid cleaning solutions.

Term (Index)	Definition
wet cleaning	
APM	
DHF	dilute HF; SiO2 etching solution of 49% HF in water; typical mixture: 1 part HF : 100 parts H2O.
dry cleaning	
HPM	
megasonic agitation, megasonic scrubbing	

ozonated water	
IMEC clean	SOM+APM+dHF/HCl Reference: <u>IMEC</u>
supercritical fluid	

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